

INFORMATION DISCLOSURE CITATION

Atty. Docket No.	07553.0029	Appln. No.	10/030,656	RECEIVED
Applicant	Masaaki HAGIHARA et al.			NOV 18 2002
Filing Date	1/11/02	Group:	Unknown 1763	TC 1700

U.S. PATENT DOCUMENTS

Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
Aws	6,107,208	8/22/00	Cheng et al.	438	724	

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FOREIGN PATENT DOCUMENTS						
	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
Aws	EP 1 041 614 A1	10/4/00	EPO			Yes
Aws	EP 0 993 031 A2	4/12/00	EPO			Yes
Aws	EP 0 993 031 A3	5/3/00	EPO			Yes

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Aws	Ueno, K., et al., "Low Resistance Copper Via Technology," Advanced Interconnects and Contacts, San Francisco, CA, April 5-7, 1999, Materials Research Society Symposium Proceedings, Vol. 564, pp. 521-533
Aws	Wong, T.K.S., et al., "Fabrication of Sub-20 nm Trenches in Silicon Nitride Using CHF ₃ /O ₂ Reactive Ion Etching and Oblique Metallization," Journal of Vacuum Science and Technology: Part B, American Institute of Physics, New York, NY, Vol. 10, No. 6, pp2393-2397

Examiner	<i>Aws - Oba</i>	Date Considered	1/16/03
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*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITAN

Atty. Docket No.	07553.0029	Serial No.	10/030656
Applicant	Masaaki HAGIHARA et al.		
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U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

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	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No	
Awo	2 333 268	07/21/1999	Great Britian				
Awo	6-204191	07/22/1994	Japan			Abstract	
Awo	2,326,765	12/30/1998	Great Britian				
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Examiner <i>Allan C. Ohs</i>	Date Considered 1/16/03
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